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Sumit Agarwal is a Professor of Chemical and Biological Engineering at the Colorado School of Mines. He received his B.S. in Chemical Engineering from the Indian Institute of Technology – Varanasi in 1996. Following that, he received his M.S. and Ph.D. degrees in Chemical Engineering from the University of New Mexico in 1998 and the University of California – Santa Barbara in 2003, respectively. Dr. Agarwal's research has spanned a broad range of topics related to plasma processing of materials where he has employed in situ plasma and surface diagnostics to understand the interfacial dynamical phenomena that occur at gas-solid interfaces during material growth. Over the last decade, his work has been focused on understanding the growth mechanism during thermal and plasma-assisted atomic layer deposition (ALD) of metal oxides, metal nitrides, and metals, and atomic layer etching of Si-based dielectrics. Dr. Agarwal's group has also worked on the development of group IV nanomaterials (nanoparticles and nanowires) using plasmas for applications in energy conversion and storage.